

ABSTRACT OF DISCLOSURE

The present invention relates to a new photosensitive resin composition capable of solubility control and a pattern formation method of a double-layer structure using the same, and more particularly to a photosensitive resin composition that can control the γ -value using a new photopolymerization initiator and lower layer hardener and that can control a film thickness according to the exposure energy without pattern breakup, even with low exposure energy.

This photosensitive resin composition is useful for color filters and overcoating

materials of LCD (liquid crystal display) manufacturing processes.